

LEXANT™ RESIN OQ4320R

REGION ASIA

DESCRIPTION

LEXANT™ OQ4320R resin is a 13 MFR polycarbonate. UV stabilized. Mold release. Optical grade with UV cut-off up to 400 nm, greater optical purity than standard grades. Suitable for sunglass and sunvisor markets.

TYPICAL PROPERTY VALUES

Revision 20201125

PROPERTIES	TYPICAL VALUES	UNITS	TEST METHODS
MECHANICAL			
Tensile Stress, yld, Type I, 50 mm/min	62	MPa	ASTM D638
Tensile Strain, yld, Type I, 50 mm/min	7	%	ASTM D638
Tensile Strain, brk, Type I, 50 mm/min	130	%	ASTM D638
Flexural Stress, yld, 1.3 mm/min, 50 mm span	96	MPa	ASTM D790
Flexural Modulus, 1.3 mm/min, 50 mm span	2340	MPa	ASTM D790
IMPACT			
Izod Impact, notched, 23°C	747	J/m	ASTM D256
Falling Dart Impact (D 3029), 23°C	169	J	ASTM D3029
Instrumented Dart Impact Energy @ peak, 23°C	63	J	ASTM D3763
THERMAL			
Vicat Softening Temp, Rate B/50	154	°C	ASTM D1525
HDT, 0.45 MPa, 6.4 mm, unannealed	137	°C	ASTM D648
HDT, 1.82 MPa, 6.4 mm, unannealed	132	°C	ASTM D648
PHYSICAL			
Specific Gravity	1.2	-	ASTM D792
Water Absorption, (23°C/24hrs)	0.15	%	ASTM D570
Mold Shrinkage, flow, 3.2 mm	0.5 – 0.7	%	SABIC method
Melt Flow Rate, 300°C/1.2 kgf	12.5	g/10 min	ASTM D1238

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